

Metallic Nano Electro Mechanically Actuated Gripper and Tunable Nano Photonic Device

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- **Nanoelectromechanical systems (NEMS)**
 - Possible to realize smaller mechanical, biological and chemical systems
- **Nano grippers**
 - Actuators for nano manipulation devices/systems
 - Relatively large displacement with low actuation voltages
- **Tunable Nano Photonic Devices**
 - **New functionalities** unachievable with passive nano photonic devices.
 - **Real-time, on-demand control** can greatly enhance the functionality of photonic devices and systems.

■ UTD Clean Room

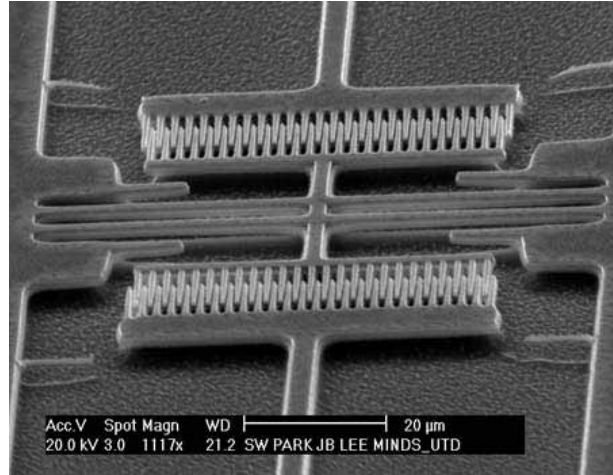
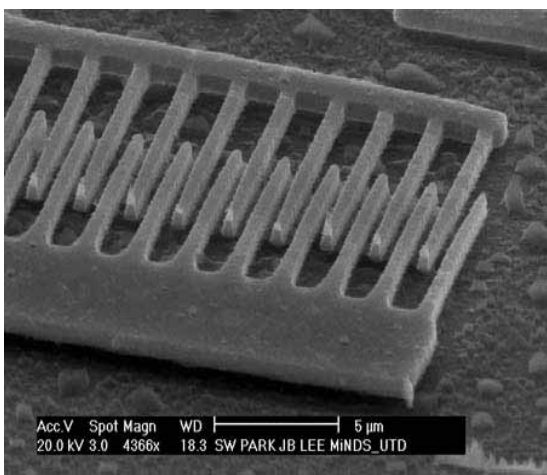
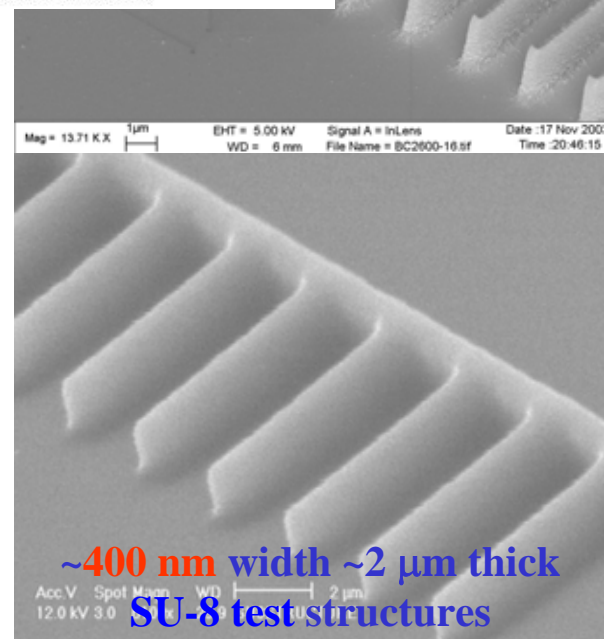
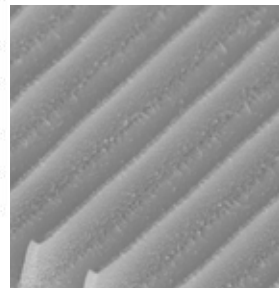
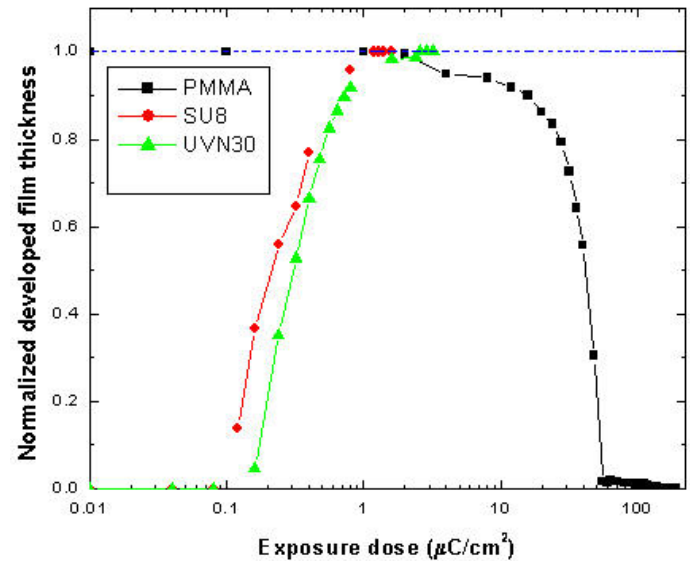
- 5,866 sq. ft. class 1,000 and 100
- Equipped with various processing and metrology equipment including evaporators, sputters, RIE, PECVD, LPCVD, mask aligners, e-beam lithography system, SEM, AFM, ellipsometer, Flexus, etc.

■ UTD's Nano Research Facilities

- Dual beam FIB, XPS, TEM, Field Emission SEM w/ E0beam Lithography System, Ultra High Vacuum Wafer Bonding System, Diamond coating CVD system

E-beam lithography

- Positive PR (e.g., PMMA)
 - Ideal for lift off.
- Negative PR (SU-8, UVN-30)
 - Very small exposure dose ($\sim 1 \mu\text{C}/\text{cm}^2$), **a factor 100 times smaller dose** (exp. time)!



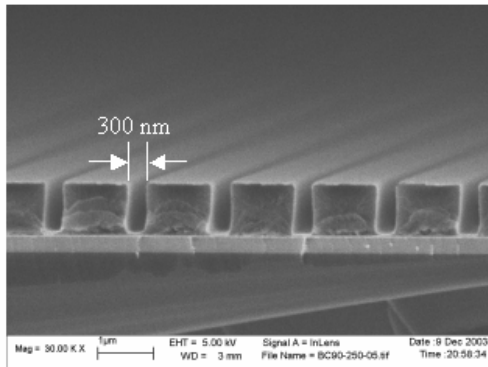
500 nm width/spacing and 500 nm thick gold comb-drive

Process

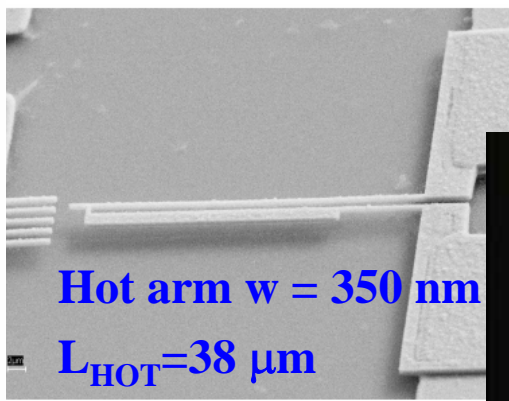
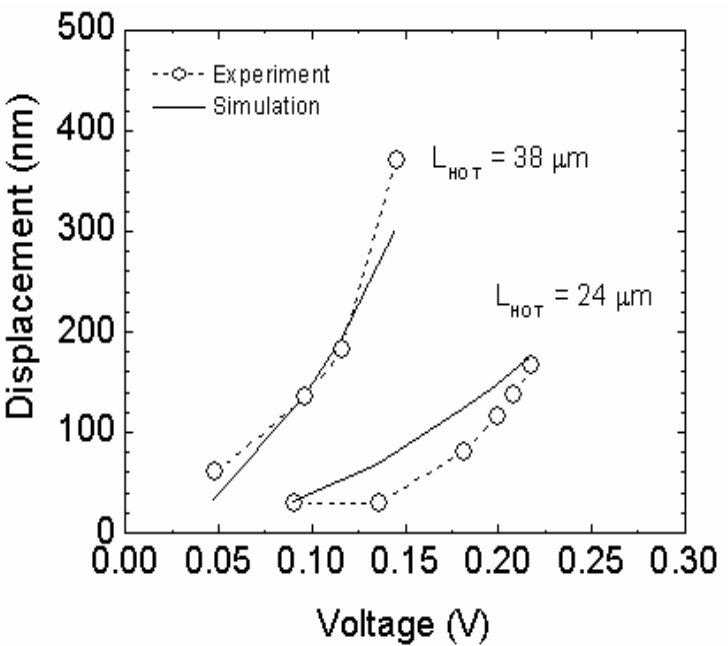
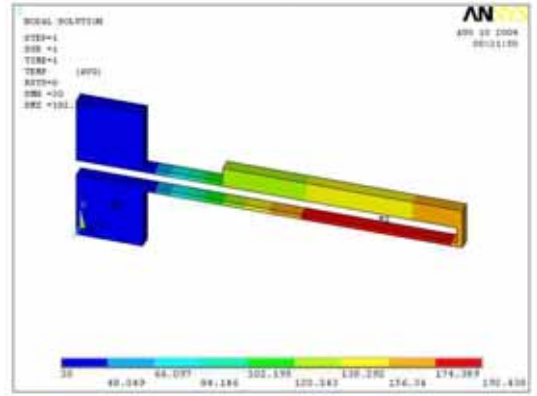
- Electron beam exposure for PMMA
- Electroplate nickel ~ 1 hr for $1 \mu\text{m}$
- Removal of PMMA by oxygen RIE

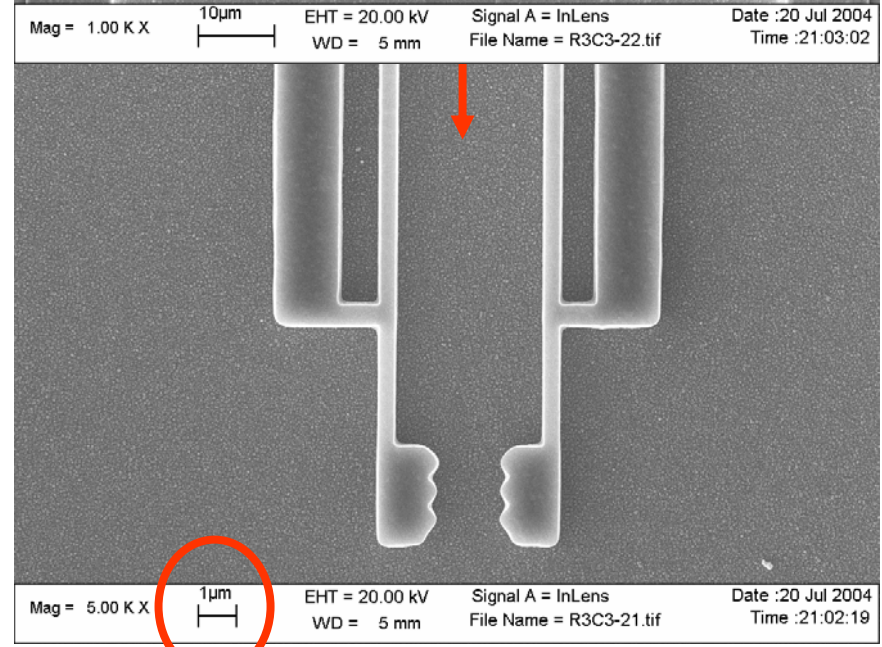
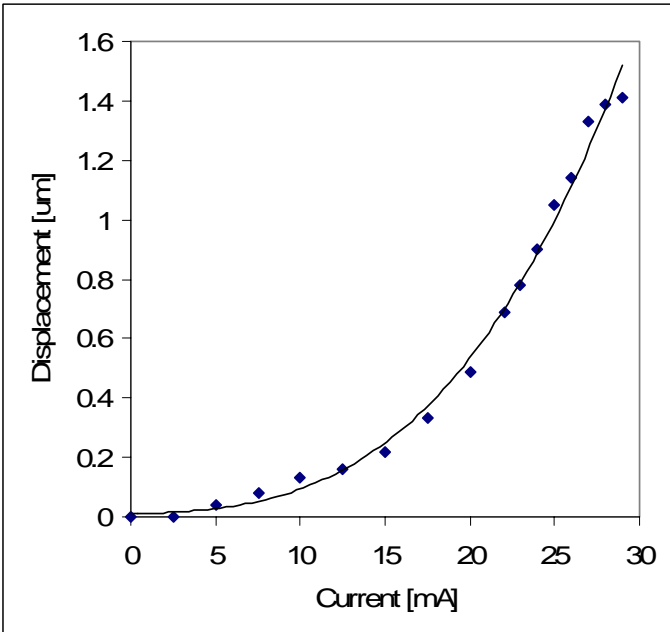
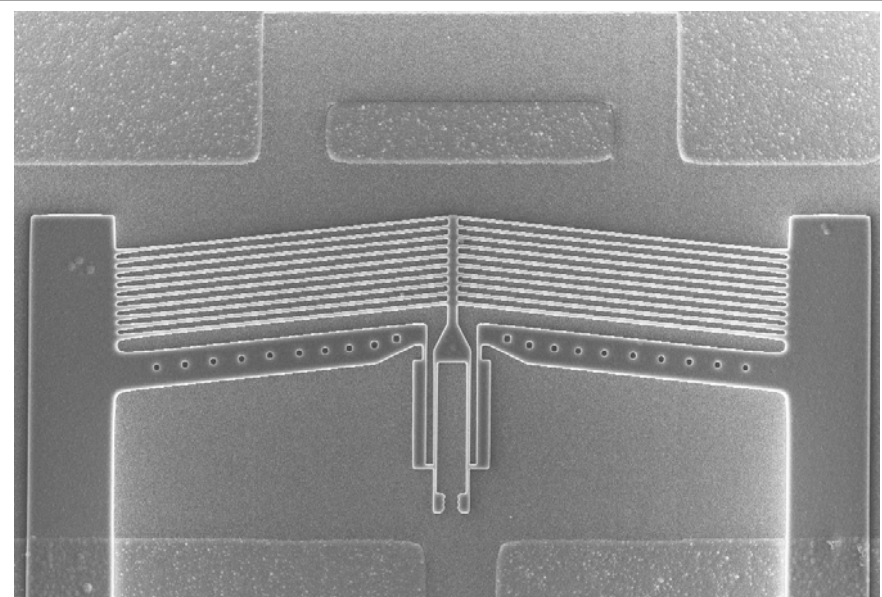
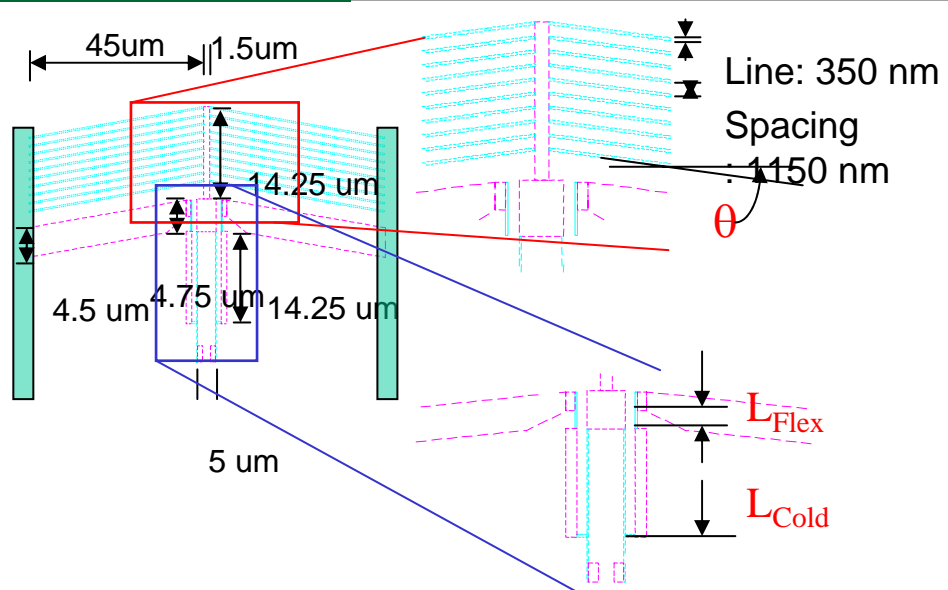
Sub-micron thermal actuator

- Reproducible displacement results
 - Type "A": 370 nm by 146 mV



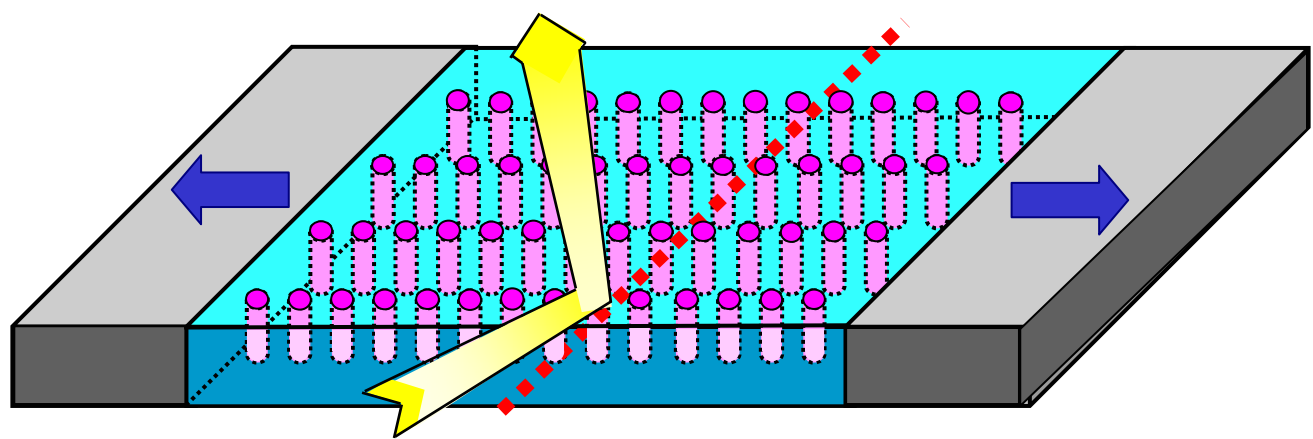
3:1 aspect ratio
 $1 \mu\text{m}$ thick PMMA mold

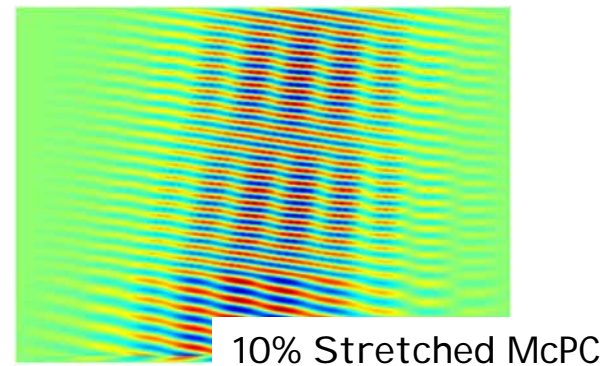
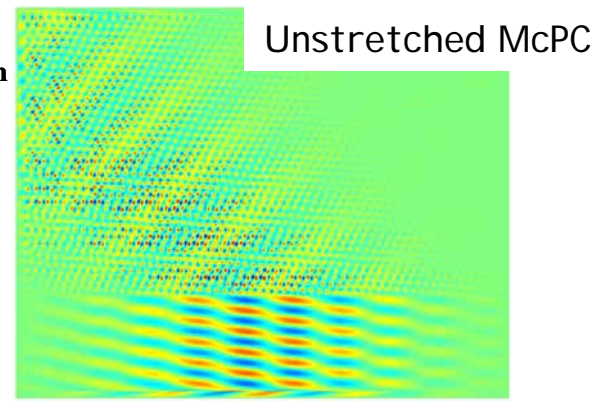
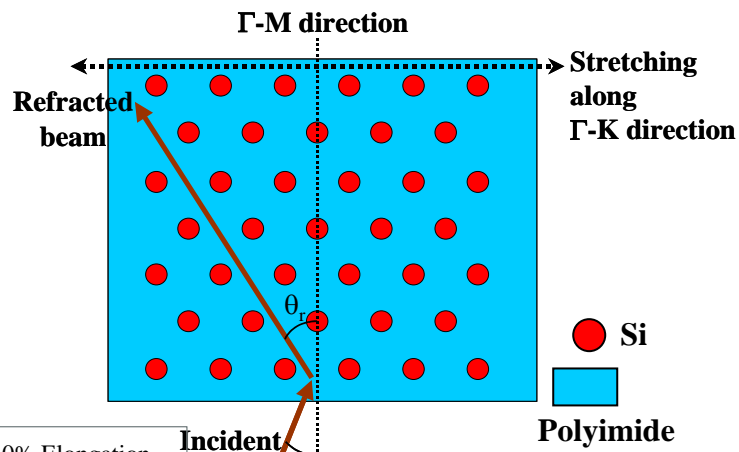




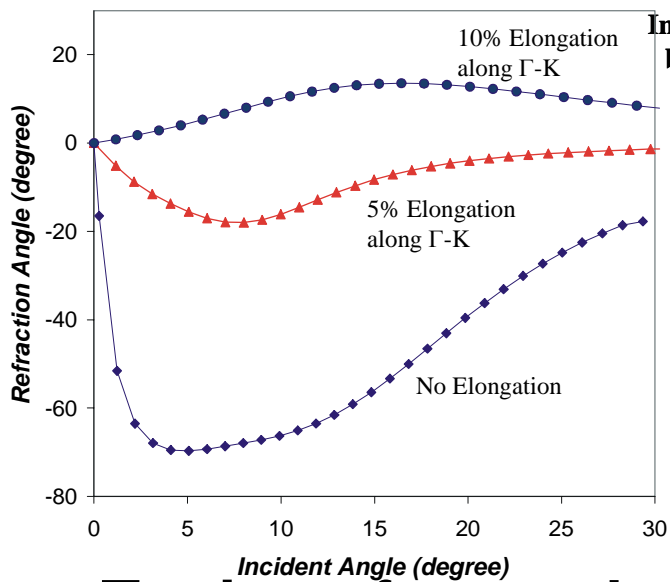
- What is **photonic crystal**?
 - Dielectric materials with a periodically varying index of refraction
 - Photons behaves similar to electrons in a semiconductor crystal; their behavior can be described by a photonic band structure
 - Ability to control/manipulate the flow of electromagnetic waves.
- **Tunable Photonic Crystal: conventional approaches**
 - Tuning by electro-optic materials (e.g. liquid crystal)
 - Tunability is very limited due to small attainable changes in refractive index ($\Delta n/n < 15\%$).
- **Our approach**
 - A radically different approach - **Mechanical tuning**
 - Photonic bands are extremely sensitive to physical changes in the photonic crystal structure.
 - **Wide tunability by mechanical force**
 - **Mechanically Controlled Photonic Crystal (McPC)**

- McPC structure is
 - Composed of Si rods embedded in flexible polymer such as Polyimide
 - Mechanical tuning by stretching/releasing McPC with NEMS/MEMS actuators
- The new material structure is compatible with the conventional semiconductor technology
 - In terms of both fabrication process and materials



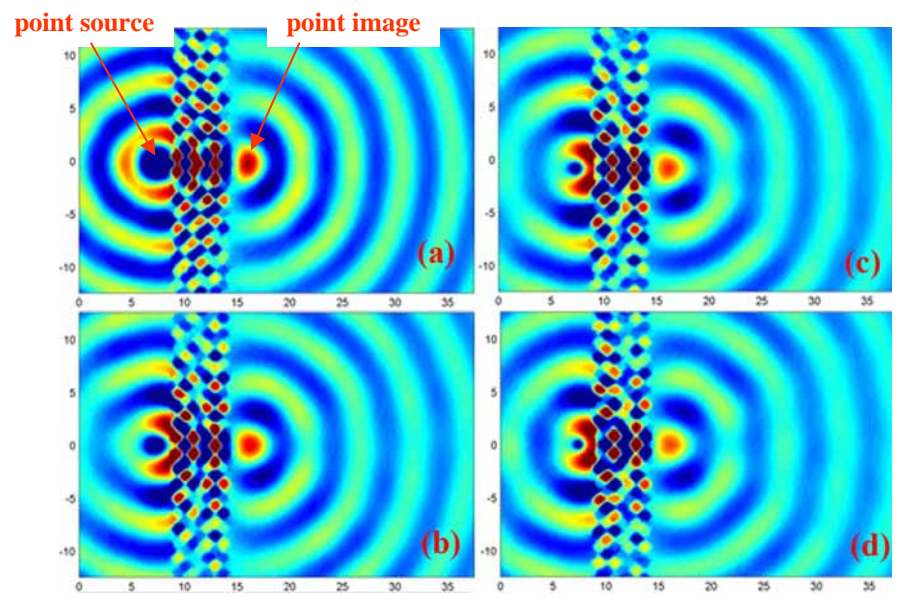
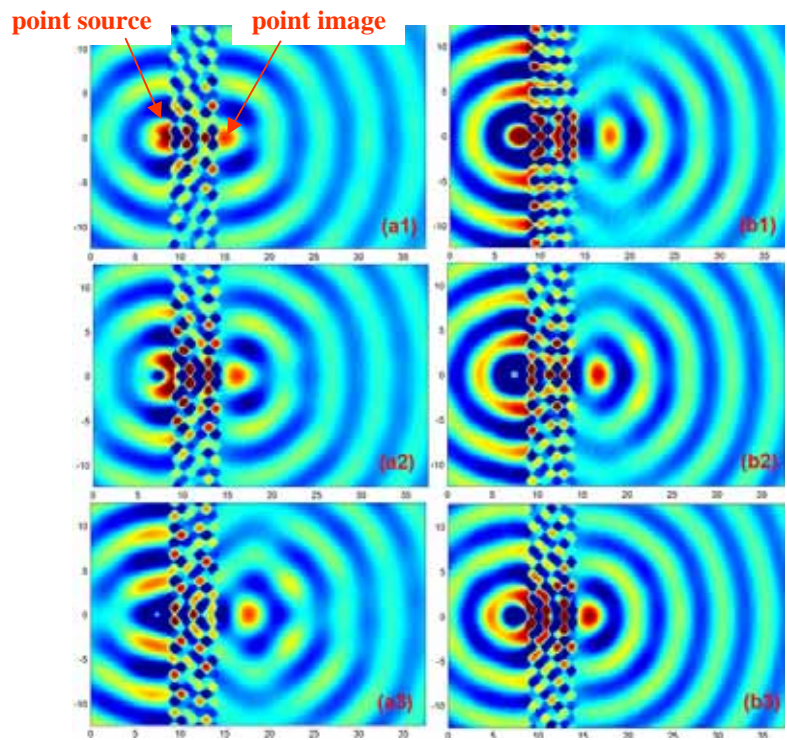


$\theta_i = 12^\circ$
 $\omega a / 2\pi c = 0.39$



- Tuning of more than 70° with small mechanical stress (~10%)
- Switching between positive & negative refraction regimes

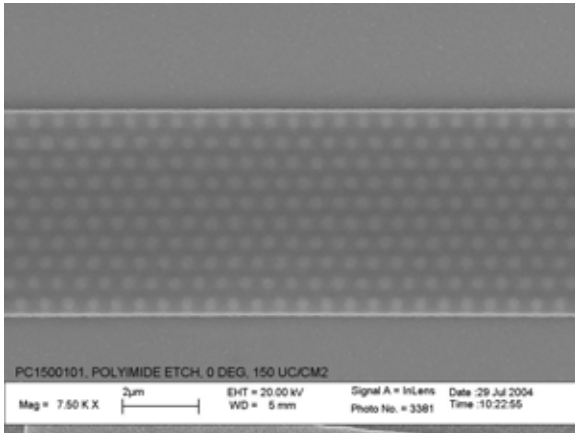
- Sub-wavelength resolution, tunability allows
 - changing focal lengths for adjustable working distance and
 - dynamically selecting the desired wavelength or scanning over a range of frequencies.



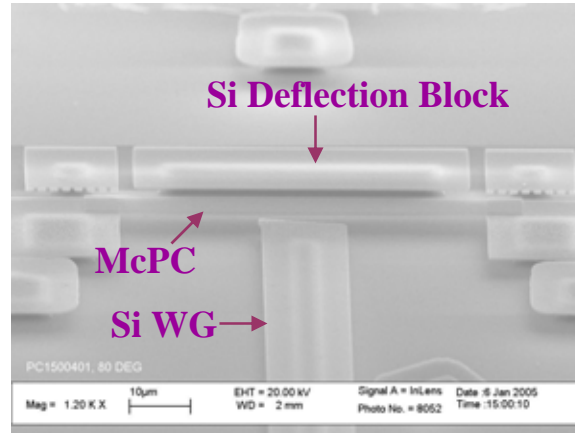
Can adjust focal length

Can also maintain identical focusing characteristics over wide frequency Range with $\Delta\omega/\omega_0$ up to 30%.

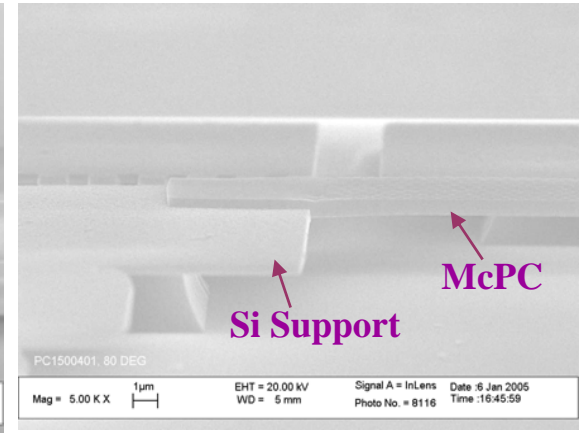
Si Pillar Matrix Embedded In Polyimide Film



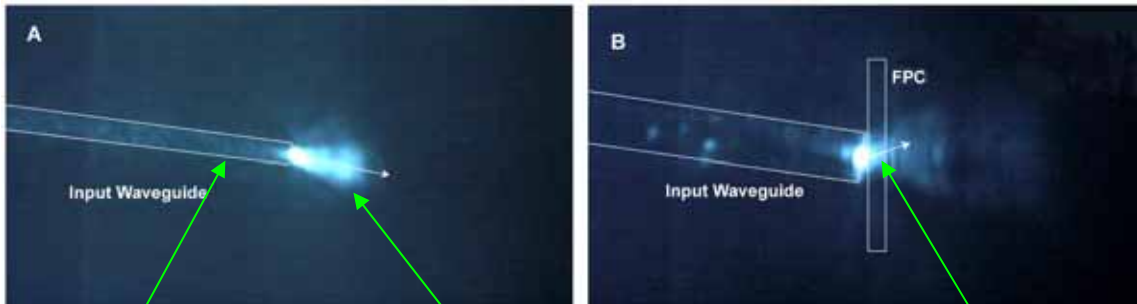
Air Suspended McPC Membrane with Si Ridge Waveguide for In-Coupling



Magnified View of Joint Region



Negative Refraction Observed in McPC

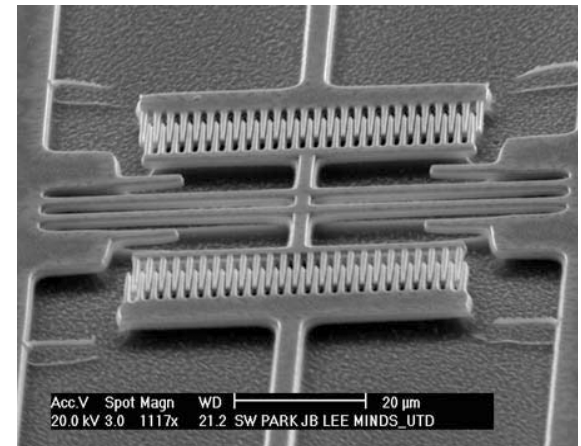


Si input waveguide inclined 6° from Horizontal ($\lambda = 1.54 \mu\text{m}$)

light coupling out to free space : no refraction

light coupling in to McPC : negative refraction

Sub- μm Comb Drive Actuator



■ 3D FPCs

- Multispectral sensing and detection over extremely wide range of frequency.

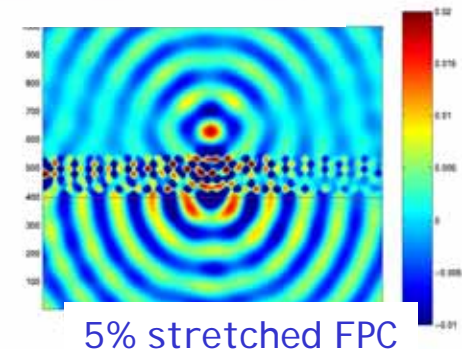
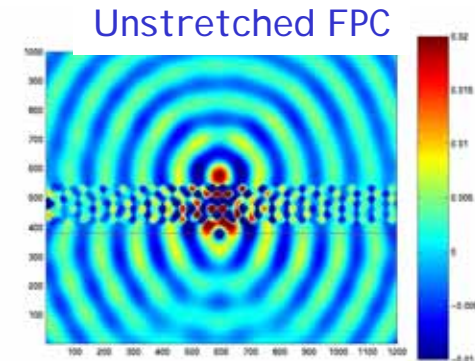
Operating Frequency	Feature size	Fabrication
Visible & Near-IR	200 ~ 500 nm	e-beam lithography, reactive ion etch (RIE)
Mid & Far-IR	0.5 ~ 10 μm	UV lithography, RIE
Terahertz	10 ~ 50 μm	UV lithography, Si Deep RIE

■ Wide range beam steering device

- Electronically tunable giant negative refraction in 2D slab PC

■ Tunable sub-wavelength focusing lens

- NIM can enable sub-wavelength focusing
- But the focusing property is strongly wavelength-dependent.
- Tunability allows dynamically selecting the desired wavelength or scanning over a range of frequencies.



- Funding
 - National Science Foundation CAREER AWARD
 - National Science Foundation Nanoscale Exploratory Research Program
 - NIST ATP Program
- Contributions
 - UTD MiNDs former/current Lab members
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- Material donation, characterization supports
 - Zyvex, TePla America, MicroChem
- Other supports
 - UTD Clean room staffs